

IN THE CLAIMS

Please cancel claims 8 and 9

Please amend the following claims.

1. (Currently Amended) An electronic device comprising:
 - a substrate having at least one build up layer embedded within,
a semiconductor die, and
at least one interconnect disposed between the substrate and the
semiconductor die,
wherein the substrate is bonded with the semiconductor die by the at least
one interconnect,
wherein the at least one build up layer comprises at least one binder and
at least one filler, and
wherein the at least one filler has a negative coefficient of thermal
expansion.
2. (Original) The electronic device of claim 1, wherein the at least one filler
comprises zirconium tungstate.
3. (Original) The electronic device of claim 2, wherein the zirconium
tungstate is a crystalline compound having a nearly isotropic coefficient of
thermal expansion of approximately -4.9ppm/degree C or less over at least the
temperature range of -50 degrees C to +250 degrees C.
4. (Original) A substrate for use in an electronic device, comprising:
 - a core;

at least one conductive layer;
at least one build up layer having at least one binder and at least one filler embedded within said substrate, wherein the at least one filler has a negative coefficient of thermal expansion.

5. (Original) The substrate of claim 4, wherein the at least one filler comprises zirconium tungstate.
6. (Original) The substrate of claim 5, wherein the zirconium tungstate is a crystalline compound having a nearly isotropic coefficient of thermal expansion of approximately -4.9ppm/degree C or less over at least the temperature range of -50 degrees C to +250 degrees C.

7. (Currently Amended) A material for use as a build up dielectric layer for a substrate, comprising:

at least one binder, and
at least one filler,
wherein the at least one filler ~~has a negative coefficient of thermal expansion~~ comprises zirconium tungstate;
wherein the zirconium tungstate is a crystalline compound having a nearly isotropic coefficient of thermal expansion of approximately -4.9ppm/degree C or less over the temperature range of -50 degrees C to +250 degrees C.

8. (Cancel)
9. (Cancel)
10. (Previously Presented) An electronic device comprising:
a semiconductor die,
a next level package,
at least one interconnect disposed between the semiconductor die and the

next level package, and

an underfill disposed at least in part between the semiconductor die and the next level package,

wherein the semiconductor die is bonded with the next level package by the at least one interconnect,

wherein the semiconductor die is bonded with the next level package by the underfill,

wherein the underfill comprises at least one binder and at least one filler, and wherein the at least one filler comprises zirconium tungstate; wherein the zirconium tungstate is a crystalline compound having a nearly isotropic coefficient of thermal expansion of approximately -4.9ppm/degree C or less over the temperature range of -50 degrees C to +250 degrees C.

11. (Cancel)

12. (Previously Presented) The electronic device of claim 10, wherein the underfill is a no-flow underfill.

13. (Cancel)

14. (Previously Presented) A method of bonding a semiconductor die with a next level package, comprising:

providing at least one interconnect;

providing an underfill material having at least one binder and at least one filler,

wherein the at least one filler comprises zirconium tungstate;

wherein the zirconium tungstate is a crystalline compound having a nearly isotropic coefficient of thermal expansion of approximately -4.9ppm /degree C or less over the temperature range of -50 degrees C to +250 degrees C;

arranging the semiconductor die, the next level package, the at least one interconnect and the underfill material such that the at least one interconnect is disposed so as to be capable of joining the semiconductor die with the next level package and such that the underfill material is disposed at least in part between the semiconductor die and the next level package;

causing the at least one interconnect to bond the semiconductor die with the next level package; and

causing the underfill material to bond the semiconductor die with the next level package.

15. (Cancel)

16. (Cancel)

17. (Currently Amended) An electronic system comprising:

an electronic device having a substrate, the substrate having at least one build up layer and at least one conductive layer embedded within,

wherein the build up layer comprises at least one binder and at least one filler, and

wherein the at least one filler has a negative coefficient of thermal expansion.

18. (Original) The electronic system of claim 17, wherein the at least one filler comprises zirconium tungstate.

19. (Original) The electronic system of claim 18, wherein the zirconium tungstate is a crystalline compound having a nearly isotropic coefficient of thermal expansion of approximately -4.9ppm/degree C or less over the temperature range of -50 degrees C to +250 degrees C.

20. (Original) An electronic system comprising:

an electronic device having a semiconductor die bonded with a next level package by an underfill disposed at least in part between the semiconductor die and the next level package,

wherein the underfill comprises at least one binder and at least one filler,

wherein the at least one filler comprises crystalline zirconium tungstate having a nearly isotropic coefficient of thermal expansion of approximately -4.9ppm/degree C or less over the temperature range of -50 degrees C to +250 degrees C.

21. (Previously Presented) The electronic system of claim 20, wherein the next level package is chosen from the group comprising of substrates, interposers, printed wiring boards, and printed circuit boards.

22. (Currently Amended) A method of making an electronic device comprising:

providing a substrate having at least one build up layer embedded within;

providing a semiconductor die, and

forming at least one interconnect disposed between the substrate and the semiconductor die,

wherein the substrate is bonded with the semiconductor die by the at least one interconnect,

wherein the at least one build up layer comprises at least one binder and at least one filler, and

wherein the at least one filler has a negative coefficient of thermal expansion.

23. (Previously Presented) The method of claim 22, wherein
the at least one filler comprises zirconium tungstate.